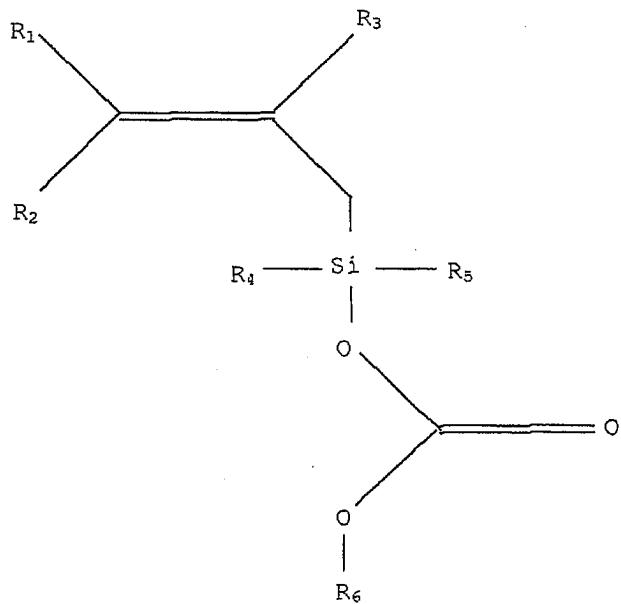


In the Claims:

1-13. (Canceled)

14. (Currently Amended) A polymerizable composition for the production of a resist, comprising at least one unsaturated, polymerizable monomer having at least one silicon atom and at least one carbonyl group, a monomer of the general formula:



wherein:

R₁, is selected from the group consisting of H and alkyl radicals;

R₂, is selected from the group consisting of H and alkyl radicals;

R₃ is selected from the group consisting of H and alkyl radicals;

R₄ comprises alkyl radicals and/or a silicon-containing compound;

R₅ comprises alkyl radicals and/or a silicon-containing compound;

R₆ comprises alkyl radicals; and

wherein R₁, R₂, R₃, R₄, R₅, and R₆ are either identical or different from one another, and

wherein either R₄ or R₅ or both comprise a silicon-containing compound.

15. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein at least one of R₁, R₂, R₃ comprises a methyl radical.

16. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein at least one of R₄ and R₅ comprises a methyl radical or siloxane.

17. (Previously Presented) The polymerizable composition as claimed in claim 14 wherein R₆ comprises a tert-butyl radical.

18. (Previously Presented) The polymerizable composition as claimed in claim 14, wherein at least one alkyl radical has a chain length of C₁ to C₈.

19. (Previously Presented) A polymer prepared by polymerization of at least the composition as claimed in claim 14.

20-33. (Canceled)